## **Amendments to the Claims:**

This listing of claims will replace all prior versions, and listings, of the claims in the application:

## **Listing of Claims:**

1. (currently amended) A method for evaluating a feature, comprising: receiving an image of the feature;

determining respective coordinates of a plurality of points on an edge of the feature in the image;

fitting a figure having a non-circular <u>and non-linear</u> shape to the plurality of points; <u>thereafter determining</u> respective distances between the plurality of points and the figure <u>having the non-circular and non-linear shape</u>; and

computing a roughness parameter for the feature <u>using the</u> in response to the respective distances.

- 2. (currently amended) The method according to claim 1, wherein computing the roughness parameter comprises computing a contact edge roughness (CER) in response to <u>based</u> on a sum of the squares of the respective distances and a number of degrees of freedom of the figure.
- 3. (currently amended) The method according to claim 1, wherein computing the roughness parameter comprises computing a correlation length (CL) in response to <u>based on</u> a sum of the squares of the respective distances, a number of degrees of freedom of the figure, and an average of squares of differences of the respective distances.
- 4. (currently amended) The method according to claim 1, wherein computing the roughness parameter comprises performing a Fourier analysis of the respective distances, and generating a power spectrum in response to based on the analysis.
- 5. (original) The method according to claim 4, wherein generating the power spectrum comprises filtering results of the Fourier analysis.

- 6. (currently amended) The method according to claim 5, wherein filtering the results comprises selecting a filter in response to based on a process used to form the feature.
- 7. (currently amended) The method according to claim 1, wherein the feature is formed on a substrate, and wherein the feature and the substrate are <del>comprised</del> in a semiconductor wafer.
- 8. (original) The method according to claim 7, wherein the feature comprises a contact hole.
- 9. (original) The method according to claim 1, wherein receiving the image comprises generating the image with a scanning electron microscope.
- 10. (original) The method according to claim 1, wherein the figure comprises an ellipse.
- 11. (original) The method according to claim 1, wherein the figure has a known shape.
- 12. (original) The method according to claim 1, wherein fitting the figure comprises determining a nominal shape of the figure by averaging at least some of the plurality of the points.
- 13. (currently amended) The method according to claim 1, wherein the figure is selected from a closed figure and an open figure is a closed figure.
- 14. (currently amended) The method according to claim 1, wherein the distance is ehosen from a perpendicular distance [[and]] or a radial distance.
- 15. (currently amended) The method according to claim 1, wherein the feature is chosen from a reticle, a part of the reticle, [[and]] or a cast of a structure.
  - 16. (currently amended) A method for evaluating a feature, comprising:

receiving an image of the feature;

determining respective coordinates of a first plurality of points on a first edge of the feature in the image;

fitting a first figure having a first non-circular <u>and</u> non-linear shape to the first plurality of points;

determining respective coordinates of a second plurality of points on a second edge of the feature in the image;

fitting a second figure having a second non-circular <u>and</u> non-linear shape to the second plurality of points;

thereafter determining respective distances between the first plurality of points and the first figure having the first non-circular and non-linear shape and respective distances between the second plurality of points and the second figure having the second non-circular and non-linear shape distances between the first and the second figures; and

computing a roughness parameter for the feature in response to the respective distances.

17. (currently amended) Apparatus for evaluating a feature, comprising: an imaging unit which is adapted to generate an image including the feature; and a processor which is adapted to:

determine respective coordinates of a plurality of points on an edge of the feature in the image,

fit a figure having a non-circular <u>and non-linear</u> shape to the plurality of points, <u>thereafter determine</u> respective distances between the plurality of points and the figure <u>having the non-circular and non-linear shape</u>, and

compute a roughness parameter for the feature in response to the respective distances.

18. (currently amended) The apparatus according to claim 17, wherein computing the roughness parameter comprises computing a contact edge roughness (CER) in response to <u>based</u> on a sum of the squares of the respective distances and a number of degrees of freedom of the figure.

- 19. (currently amended) The apparatus according to claim 17, wherein computing the roughness parameter comprises computing a correlation length (CL) in response to <u>based on</u> a sum of the squares of the respective distances, a number of degrees of freedom of the figure, and an average of squares of differences of the respective distances.
- 20. (currently amended) The apparatus according to claim 17, wherein computing the roughness parameter comprises performing a Fourier analysis of the respective distances, and wherein the processor is adapted to generate a power spectrum in response to based on the analysis.
- 21. (original) The apparatus according to claim 20, wherein generating the power spectrum comprises filtering results of the Fourier analysis.
- 22. (currently amended) The apparatus according to claim 21, wherein filtering the results comprises selecting a filter in response to based on a process used to form the feature.
- 23. (currently amended) The apparatus according to claim 17, wherein the feature is formed on a substrate, and wherein the substrate and the feature are comprised in a semiconductor wafer.
- 24. (original) The apparatus according to claim 23, wherein the feature comprises a contact hole.
- 25. (original) The apparatus according to claim 17, wherein the imaging unit and the processor are comprised in a scanning electron microscope.
- 26. (original) The apparatus according to claim 17, wherein the figure comprises an ellipse.
- 27. (original) The apparatus according to claim 17, wherein the figure has a known shape.

- 28. (original) The apparatus according to claim 17, wherein the processor is adapted to determine a nominal shape of the figure by averaging at least some of the plurality of the points.
- 29. (currently amended) The apparatus according to claim 17, wherein the figure is selected from a closed figure and an open figure.
- 30. (currently amended) The apparatus according to claim 17, wherein the distance is chosen from a perpendicular distance [[and]] or a radial distance.
- 31. (currently amended) The apparatus according to claim 17, wherein the feature is chosen from a reticle, a part of the reticle, [[and]] or a cast of a structure.
  - 32. (Currently amended) Apparatus for evaluating a feature, comprising: an imaging unit which is adapted to generate an image including the feature; and a processor which is adapted to:

determine respective coordinates of a first plurality of points on a first edge of the feature in the image,

fit a first figure having a first non-circular <u>and</u> non-linear shape to the first plurality of points,

determine respective coordinates of a second plurality of points on a second edge of the feature in the image,

fit a second figure having a second non-circular <u>and</u> non-linear shape to the second plurality of points,

thereafter determine distances between the first plurality of points and the first figure having the first non-circular and non-linear shape and respective distances between the second plurality of points and the second figure having the second non-circular and non-linear shape distances between the first and the second figures, and

compute a roughness parameter for the feature in response to the respective distances.

33. (currently amended) A method for evaluating a feature, comprising:

receiving an image of the feature;

determining respective coordinates of a plurality of points on an edge of the feature in the image;

fitting a figure having a non-circular and non-linear shape to the plurality of points;

thereafter determining respective distances between the plurality of points and the figure having the non-circular and non-linear shape; and

computing a correlation length in response to <u>based on</u> a sum of the squares of the respective distances, a number of degrees of freedom of the figure, and an average of squares of differences of the respective distances.

34. (currently amended) A method for evaluating a feature, comprising: receiving an image of the feature;

determining respective coordinates of a plurality of points on an edge of the feature in the image;

fitting a figure having a non-circular and non-linear shape to the plurality of points;

<u>thereafter</u> determining respective distances between the plurality of points and the figure <u>having the non-circular and non-linear shape;</u>

performing a Fourier analysis of the respective distances; and

filtering results of the Fourier analysis <u>based on in response to</u> a process used to form the feature.

35. (Currently amended) A method for evaluating a feature, comprising: receiving an image of the feature;

determining respective coordinates of a plurality of points on an edge of the feature in the image;

fitting a figure having a non-circular and non-linear shape to the plurality of points;

thereafter determining respective distances between the plurality of points and the figure having the non-circular and non-linear shape;

performing a Fourier analysis of the respective distances; and

filtering results of the Fourier analysis in response to based on a shape of the feature.

36. (currently amended) Apparatus for evaluating a feature, comprising:

an imaging unit which is adapted to generate an image including the feature; and a processor which is adapted to:

determine respective coordinates of a plurality of points on an edge of the feature in the image,

fit a figure <u>having a non-circular and non-linear shape</u> to the plurality of points, <u>thereafter</u> determine respective distances between the plurality of points and the figure <u>having the non-circular and non-linear shape</u>, and

compute a correlation length in response to <u>based on</u> a sum of the squares of the respective distances, a number of degrees of freedom of the figure, and an average of squares of differences of the respective distances.

37. (currently amended) Apparatus for evaluating a feature, comprising: an imaging unit which is adapted to generate an image including the feature; and a processor which is adapted to:

determine respective coordinates of a plurality of points on an edge of the feature in the image,

fit a figure <u>having a non-circular and non-linear shape</u> to the plurality of points, <u>thereafter</u> determine respective distances between the plurality of points and the figure <u>having the non-circular and non-linear shape</u>,

perform a Fourier analysis of the respective distances, and filter results of the Fourier analysis in response to a process used to form the feature.

38. (currently amended) Apparatus for evaluating a feature, comprising: an imaging unit which is adapted to generate an image including the feature; and a processor which is adapted to:

determine respective coordinates of a plurality of points on an edge of the feature in the image,

fit a figure <u>having a non-circular and non-linear shape</u> to the plurality of points, <u>thereafter</u> determine respective distances between the plurality of points and the figure <u>having the non-circular and non-linear shape</u>,

perform a Fourier analysis of the respective distances, and

filter results of the Fourier analysis in response to a shape of the feature.